



## Plasma Science and Plasma-Assisted Applications

Guest Editors:

**Dr. Ying-Hao Liao**

**Dr. Kun-Mo Lin**

**Prof. Dr. Jian-Zhang Chen**

**Dr. Katsuyuki Takahashi**

Deadline for manuscript  
submissions:

**30 May 2025**

### Message from the Guest Editors

Plasma science continues to evolve and expand, driven by ongoing research and technological advancements. As our understanding of plasmas deepens, new applications and innovations are being discovered, offering exciting possibilities for addressing challenges and advancing various scientific and technological frontiers. This Special Issue on “Plasma Science and Plasma-Assisted Applications” is aimed to focus on the recent developments and research on plasma physics, plasma chemistry, plasma technology and plasma applications in, but not limited to, energy, combustion, aerospace, biology, medicine, manufacturing, fluid mechanics and environmental science.

### Keywords

- plasma technology
- plasma physics
- plasma chemistry
- plasma applications
- plasma-assisted combustion
- plasma-treated water
- plasma coating
- plasma medicine
- plasma processing
- plasma diagnostics





an Open Access Journal by MDPI

## Editor-in-Chief

### Prof. Dr. Giancarlo Cravotto

Department of Drug Science and  
Technology, University of Turin,  
Via P. Giuria 9, 10125 Turin, Italy

## Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

## Author Benefits

**Open Access:** free for readers, with article processing charges (APC) paid by authors or their institutions.

**High Visibility:** indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, AGRIS, and other databases.

**Journal Rank:** JCR - Q2 (*Engineering, Chemical*) / CiteScore - Q2 (*Chemical Engineering (miscellaneous)*)

## Contact Us

---

Processes Editorial Office  
MDPI, Grosspeteranlage 5  
4052 Basel, Switzerland

Tel: +41 61 683 77 34  
[www.mdpi.com](http://www.mdpi.com)

[mdpi.com/journal/processes](http://mdpi.com/journal/processes)  
[processes@mdpi.com](mailto:processes@mdpi.com)  
[X@Processes\\_MDPI](https://twitter.com/Processes_MDPI)